DATASHEET EBL2

EUV RADIATION

At 3 kHz:	Broad band
Power [W]	3.3
Maximum intensity [W/mm ²]	2.0
Maximum dose per Mp [kJ/mm ²]	0.6

	Minimum	Maximum
EUV spot diameter [mm]	1	30
Pulse repetition rate [Hz]	2,000	3,000

- Broad band: 10 nm to 20 nm
- Spectral Purity Filter optional
- Dose Control: <20%</p>
- Unattended exposure time: up to 100h

GAS ENVIRONMENT

- Ultra clean vacuum chamber
- Background pressure: < 5E-8 mbar
- Process gasses: H₂, He, Ar
- Max pressure at full pump speed 0.7 mbar Hydrogen
- Contamination gasses: H₂O, XCDA, O₂, N₂, Hydrocarbons
- Differentially pumped RGA

STAGE

- Positioning accuracy: <250 μm
- Reproducibility: <100 μm
- Flexible exposure spot size: 1 mm to 30 mm
- Temperature (backside sample): -20 to 120°C
- Electrical contacts on sample holder for additional sensor readout
- Integrated photodiodes
- Positioning with markers and imaging ellipsometer

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This datasheet is an indication of functionality and performance which TNO is aiming at with EBL2. TNO solely warrants functionality and performance of EBL2 to the specifications agreed at the time of sale.

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INSPECTION & METROLOGY

In-situ imaging ellipsometer:

- Field of view: 15 mm x 15 mm
- Imaging resolution: 0.1 mm
- Sensitivity: 0.3 nm of carbon

In vacuum analysis:

- XPS system (152x152 mm² sample capability)

TNO innovation for life

- Every position addressable on sample
- Monochromated AI-Ka source
- Energy resolution 0.1 eV
- Standard spot size 0.7 mm x 0.3 mm
- Smaller spot sizes possible

Other facilities at TNO lab:

- Variable Angle Spectroscopic Ellipsometer
- Optical particle inspection
- 3D backside inspection
- XRD
- SEM/EDX
- AFM
- Outgassing setup

SAMPLE SIZE

- Loading via Dual Pod interface
- Accepts SEMI P37 compliant masks
- Accepts EUV masks with pellicle
- Maintains NXE compatibility for backside particles cleanliness
- Max sample size: 152x152x20 mm³ incl. sample holder
- Automated sample handling

WAY OF WORKING

- Offering based on customer test protocol
- Exposure costs based on total applied pulses plus hours used of EBL2 excl. surface analysis (XPS), cleaning costs and sample preparation.

CONTACT

- Wilbert Staring
- wilbert.staring@tno.nl
- http://www.tno.nl/EBL2/